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PTO/SB/08A (10-96)



Substitute for form 1449A/PTO **INFORMATION DISCLOSURE STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Complete if Known

Application Number	10/750,969
Filing Date	01/05/2004
First Named Inventor	Ein-Eli
Group Art Unit	1742
Examiner Name	
Attorney Docket Number	27054

Sheet	1	Of	2
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U.S. PATENT DOCUMENTS

Examiners Initials	Cite No. ¹	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD- YYYY	Pages, columns, lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code ² (if known)			
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		Office ³	Number ⁴	Kind Code ⁵ (if known)				
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Sheet	2	Of	2
		Attorney Docket Number	27054
OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.	
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Examiner Signature			Date Considered

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